## SERIAL NO. ATTY DOCKET NO. a •= Not Yet Assigned NEC99P156-1 INFORMATION DISCLOSURE CITATION APPLICANT(S) (Use several sheets if necessary) Maeda, et al. FILING DATE GROUP **Concurrently Herewith** Not Yet Assigned **U.S. PATENT DOCUMENTS** \*EXAMINER FILING DATE DOCUMENT NUMBER DATE NAME CLASS SUBCLASS INITIAL IF APPROPRIATE **FOREIGN PATENT DOCUMENTS** TRANSLATION DOCUMENT NUMBER DATE COUNTRY CLASS SUBCLASS YES NO 2-27660 06/19/90 Japan 7-234511 09/05/95 Japan 8-259626 10/08/96 Japan 10-171122 06/26/98 Japan I NA 7-252324 10/03/95 Japan OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) Donald C. Hofer, et al., "193 nm Photoresist R&D: The Risk & Challenge", Journal of Photopolymer Science and Technology, Vol. 9, No. 3, pp. 387-397, May 16, 1996.

EXAMINER 7 M

DATE CONSIDERED

Hiroshi Ito, et al., "Applications of Photoinitiators to the Design of Resists for Semiconductor Manufacturing", American Chemical Society Symposium Series, Vol. 242, pp. 11-23, 1984.

11-19-01

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## ATTY DOCKET NO. SERIAL NO. NEC99P156-ms Not Yet Assigned INFORMATION DISCLOSURE CITATION APPLICANT(S) Maeda, et al. (Use several sheets if necessary) FILING DATE GROUP **Concurrently Herewith** Not Yet Assigned **U.S. PATENT DOCUMENTS** FILING DATE \*EXAMINER SUBCLASS CLASS DOCUMENT NUMBER DATE NAME IF APPROPRIATE INITIAL **FOREIGN PATENT DOCUMENTS** TRANSLATION DATE COUNTRY CLASS SUBCLASS DOCUMENT NUMBER YES NO WĀ 01/31/95 7-28237 Japan

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

Takechi, et al., "Alicyclic Polymer for ArF and KrF Excimer Resist Based on Chemical Amplification", Journal of Photopolymer Science and Technology, Vol. 5, No. 3, pp. 439-446, 1992.

R.D. Allen, et al., "Resolution and Etch Resistance of a Family of 193 nm Positive Resists", Journal of Photopolymer Science and Technology, Vol. 8, No. 4, pp. 623-636,1995.

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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## INFORMATION DISCLOSURE CITATION

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	OTHER DOCUM	ENTS (Includi	 ng Author, Title,	Date Pertinen	t Pages Fi			1
	R.D. Allen, et al., "Propp. 456-474, 1996.	ogress in 193 nm	Positive Resists",	Journal of Photo	polymer Scie	nce and Techno	ology, Vol. 9	), No. 3,
W	pp. 456-474, 1996.							
W	J.V. Crivello, et al., "A Arylation of Sulfides a 3055-3058, 1978.	New Preparation of Selenides with	on of Triarylsulfor h Diaryliodonium	nium and -selenon Salts", Journal o	nium Salts vi f the Organi	a the Copper (I) c Chemistry, Vo	I)-Catalyze ol. 43, No. 1	d 5, pp.
EXAMINE	R RASLA	_	DATE	CONSIDERED	1-19-01	. · · · · · · · · · · · · · · · · · · ·		
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		Concurrently Herewith	Not Yet Assigned					
*EXAMINER INITIAL	OTHER DOCUMENTS (Including Author, Title							
W	F. M. Houlihan, et al., "The Synthesis, Characteriz Photo-Acid Generators with Improved Resistance							
		Takumi Ueno, et al., "Chemical Amplification Positive Resist Systems Using Novel Sulfonates as Acid Generators", Proceeding of PME '89, Kodansha, pp. 413-424, 1990.						
	H.B. Henbest, et al., "Aspects of Stereochemistry"							
RA	S. Bechmann, et al., "Zur Kenntnis der bei der Hy Lactone", Chem. Ber., Vol. 94, pp. 48-58, 1961.	dratisierung von Bicyclo-[1.2.2]-hept	en-carbonsauren entstehenden					
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